

Notice of References Cited		Application/Control No.	Applicant(s)/Patent Under Reexamination	
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		Examiner	Art Unit	Page 1 of 1
		Walter L. Lindsay, Jr.	2812	

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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	B	US-6,156,126	12-2000	Chen et al.	438/748
	C	US-6,221,766	04-2001	Wasserman, Yuval	438/656
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NON-PATENT DOCUMENTS

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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.